Accepted Manuscript

Partial formation of linear concavo-convex microstructure onto microwells by diamond-like carbon thin film deposition

Masahito Ban, Tsuyoshi Hagiwara, Yoshizumi Masumoto

PII:	S0925-9635(16)30485-X
DOI:	doi: 10.1016/j.diamond.2017.02.021
Reference:	DIAMAT 6830
To appear in:	Diamond & Related Materials
Received date:	12 September 2016
Revised date:	24 February 2017
Accepted date:	28 February 2017



Please cite this article as: Masahito Ban, Tsuyoshi Hagiwara, Yoshizumi Masumoto, Partial formation of linear concavo-convex microstructure onto microwells by diamond-like carbon thin film deposition. The address for the corresponding author was captured as affiliation for all authors. Please check if appropriate. Diamat(2016), doi: 10.1016/j.diamond.2017.02.021

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.

ACCEPTED MANUSCRIPT

Partial Formation of Linear Concavo-convex Microstructure onto

Microwells by Diamond-like Carbon Thin Film Deposition

Masahito Ban*, Tsuyoshi Hagiwara, Yoshizumi Masumoto

Dept. of Innovative Systems Engineering, Nippon Institute of Technology,

4-1, Gakuendai, Miyashiro, Minami-saitama, Saitama, 345-8501, Japan

*Corresponding author. Tel/fax: +81 484 33 7724, E-mail address: ban@nit.ac.jp

Abstract

By a procedure to partially deposit rigid diamond-like carbon (DLC) thin films using a mask on a soft elastomer, poly(dimethylsiloxane) (PDMS), substrate directionally stretched, areas with the regular linear pattern consisting of a periodical concavo-convex shape with several µm size were successfully formed onto microwells fabricated on the substrate. The DLC thin film depositions were performed by an inductively-coupled plasma (ICP) CVD method, and the optimal deposition conditions, mainly the substrate bias voltage of -650 V, to form the linear pattern of the periodical concavo-convex shape were revealed. When an elongation strain applied on the PDMS substrate increased, the height of the concavo-convex shape increased. In Download English Version:

https://daneshyari.com/en/article/5000795

Download Persian Version:

https://daneshyari.com/article/5000795

Daneshyari.com